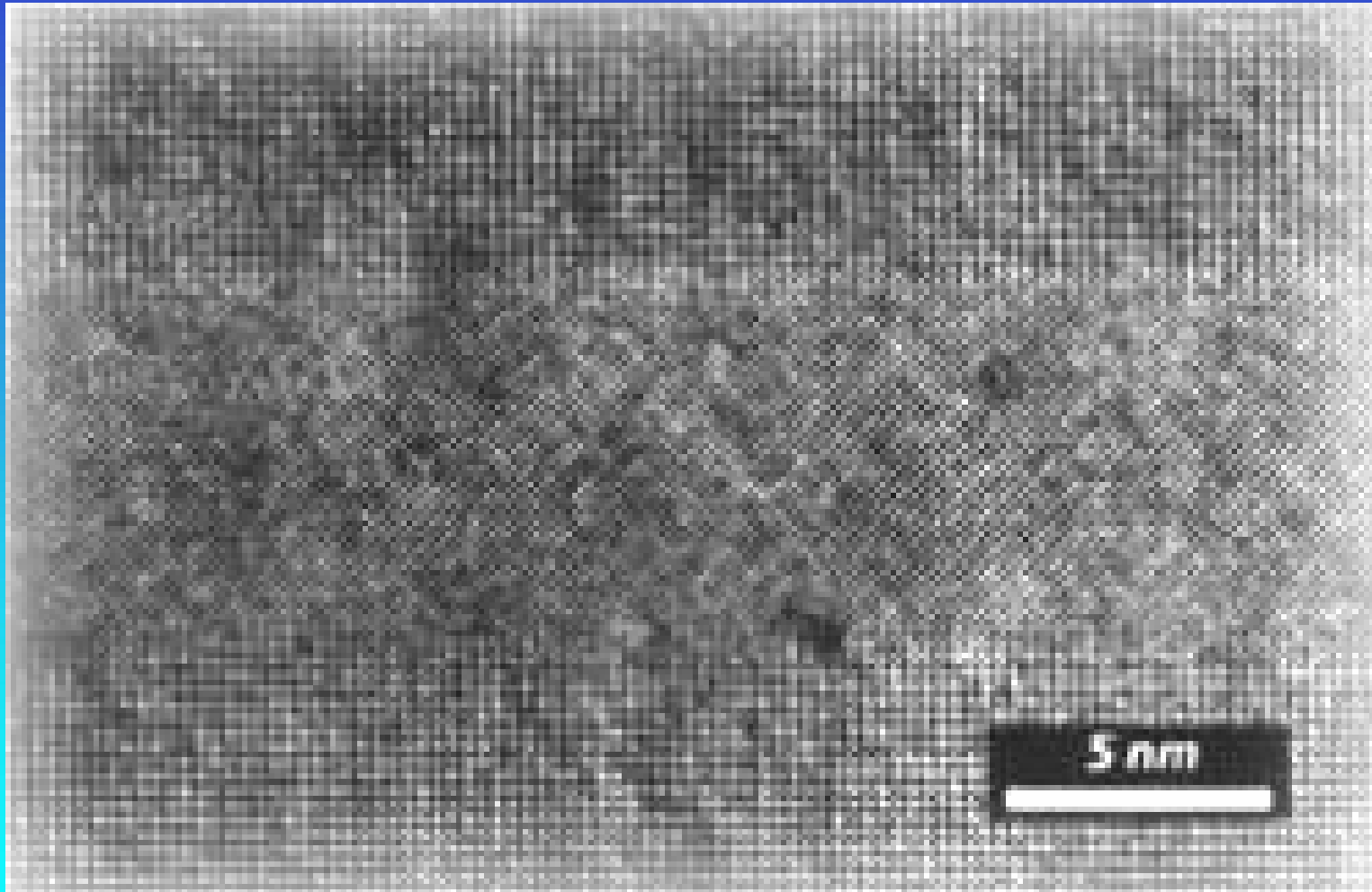
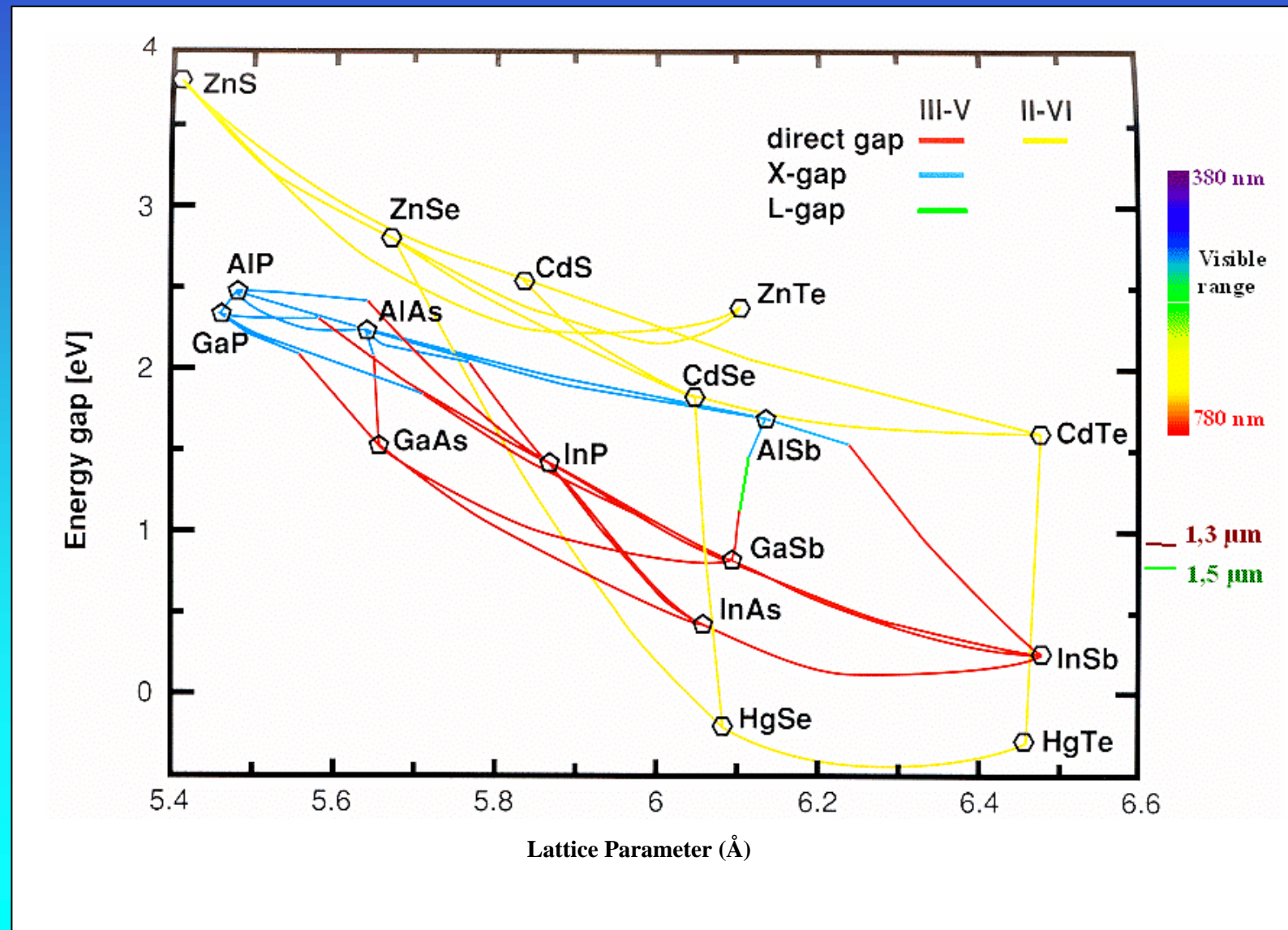


Semiconductor Heterojunctions

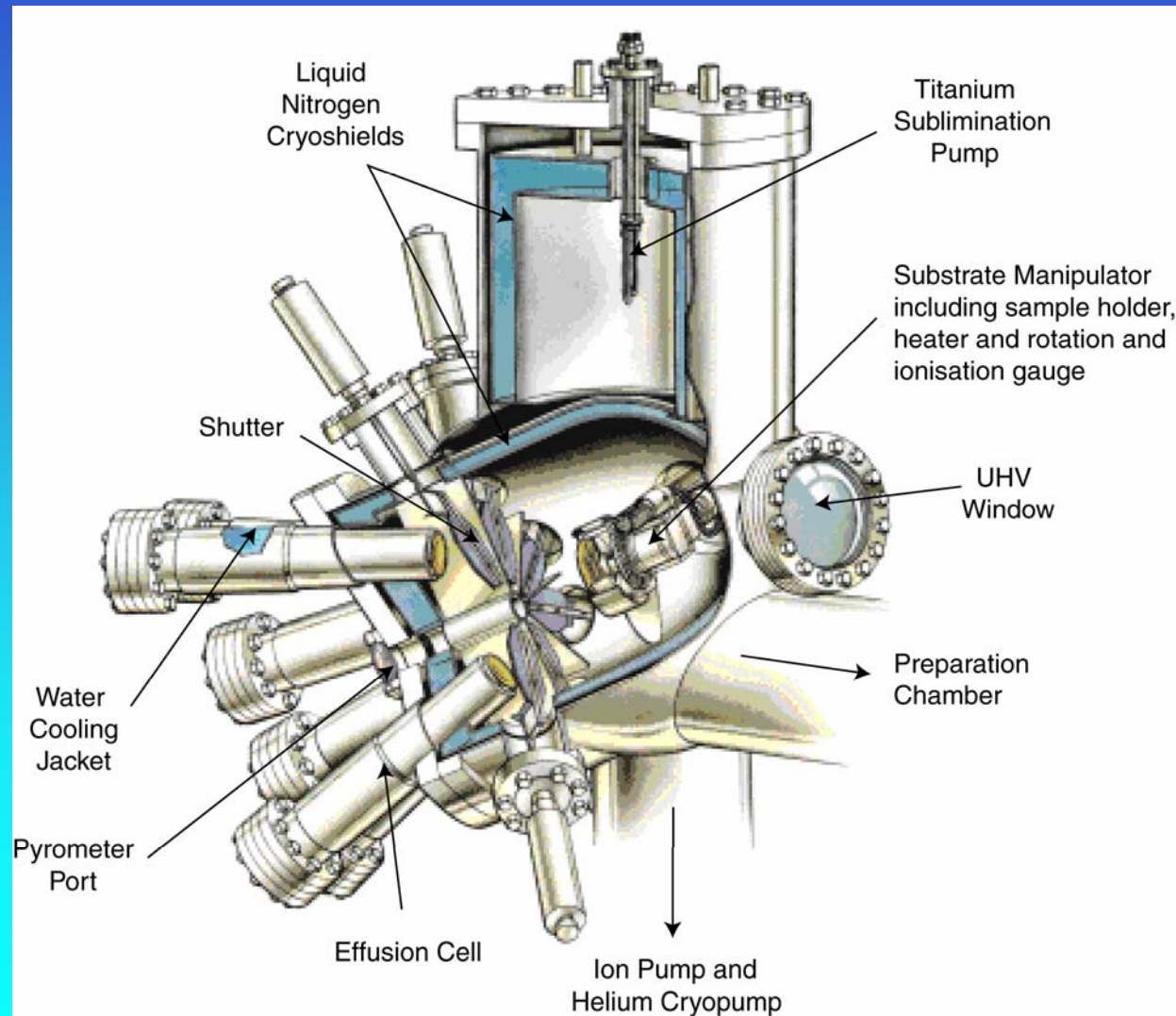


**HRTEM image of a 6.4 nm AlGaAs/InGaAs
strained layer heterostructure**

Energy gap vs lattice parameter



MBE Growth Chamber



- Growth, preparation and loadlock chambers
 - **Stainless steel**
 - **Copper gasket seals**
- Ion, turbo- and cryopumps
- LN_2 cryoshield (**400L/day**)
- Very long bakes at 200°C
- Outgassing of sources
- Outgassing of substrates
- Ultra-high vacuum
 - **10^{-11} mbar total**
- Pressure of impurities
 - **10^{-15} mbar**
- Growth of thick layers to bury contamination – up to **6 months** to clean up.

Production MBE System

VG Semicon V150

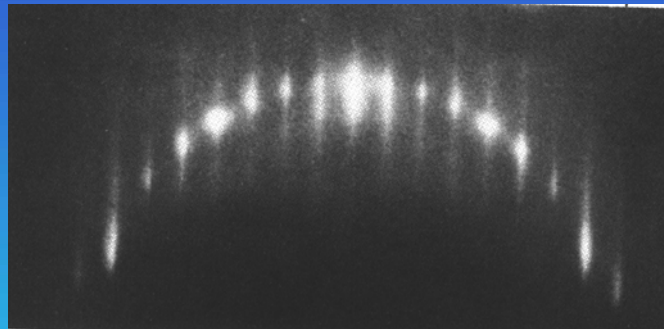
- Launched 1999
- Automated
- Simultaneous growth on four 6 inch wafers
- 20,000 6 inch wafers per year
- Laser diodes, LEDs, HBTs, PHEMTs
- Cost £2M



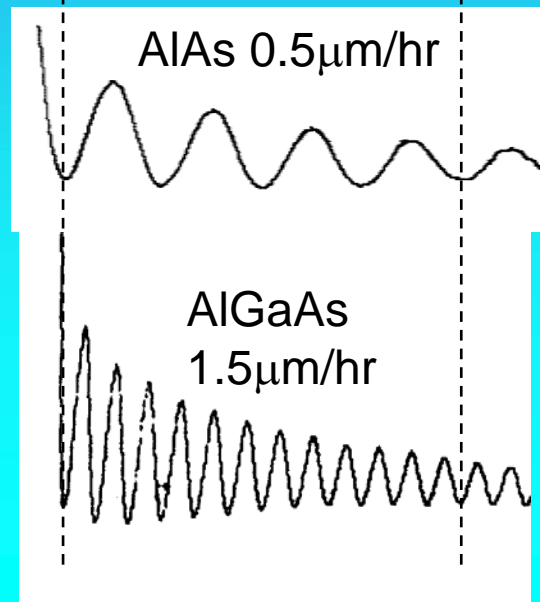
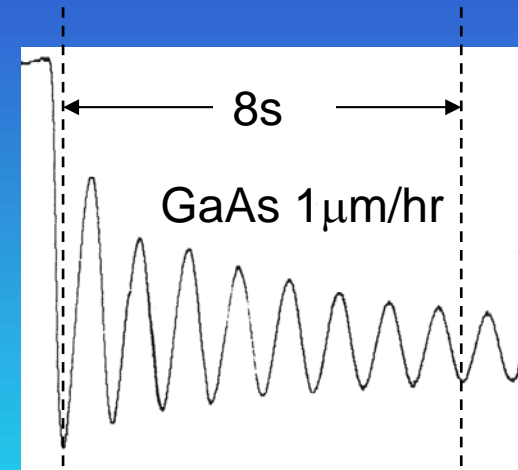
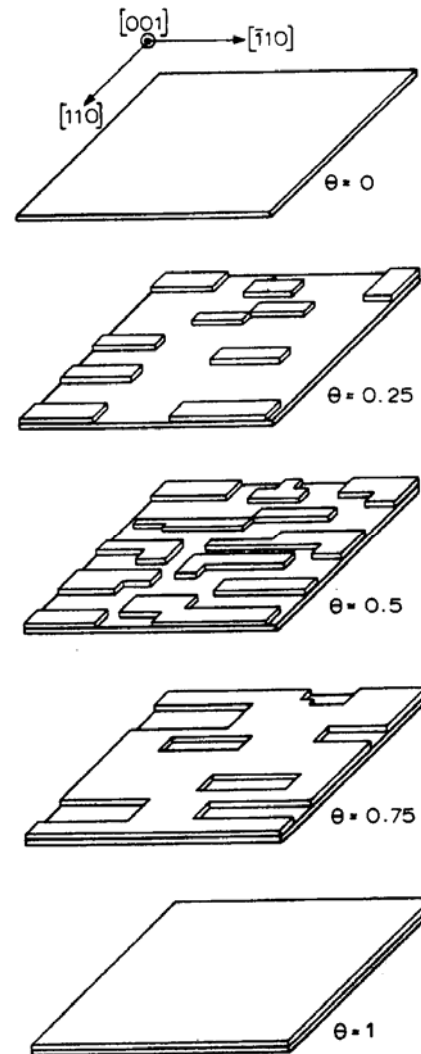
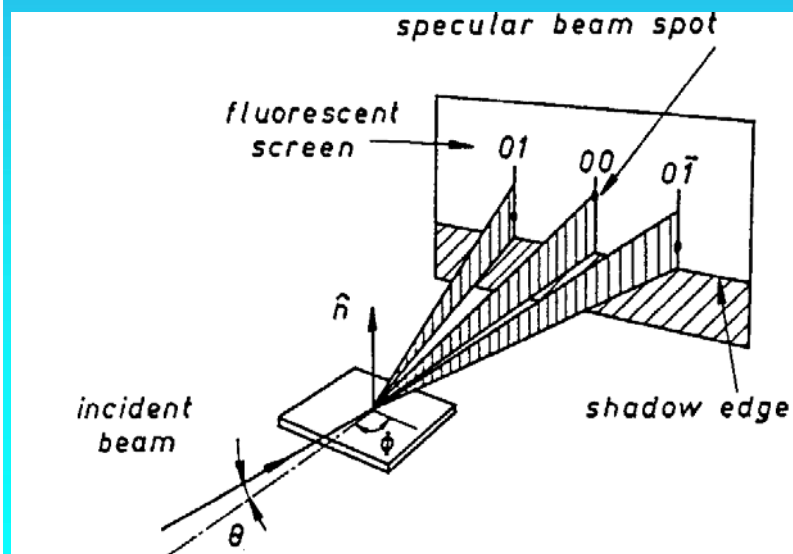
VG Semicon

RHEED Oscillations

(Observation of growth monolayer by monolayer)



2x4 pattern $(\bar{1}10)$ direction



MOCVD Growth System

- Chemical reaction of elements bonded in volatile organic compounds
- e.g. $(\text{CH}_3)_3\text{Ga} + \text{AsH}_3 \rightarrow \text{GaAs} + 3\text{CH}_4$
- Reaction takes place on a heated substrate and growth is also 'epitaxial'

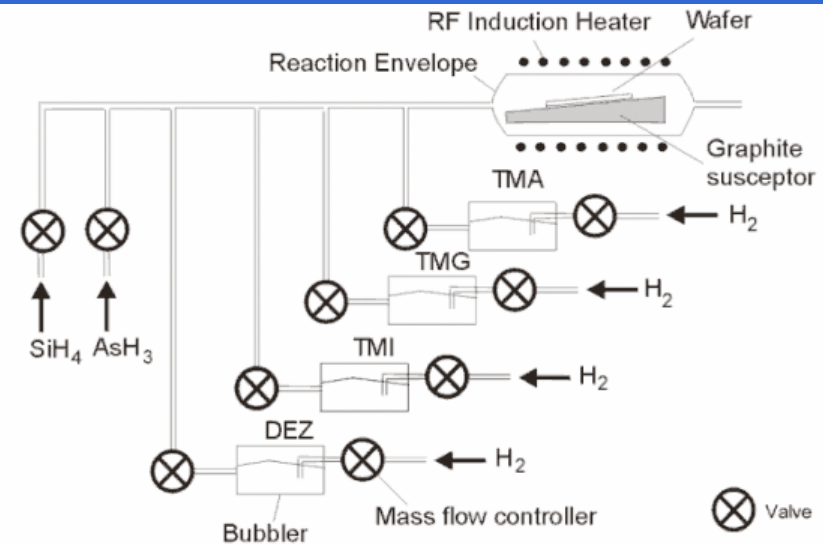
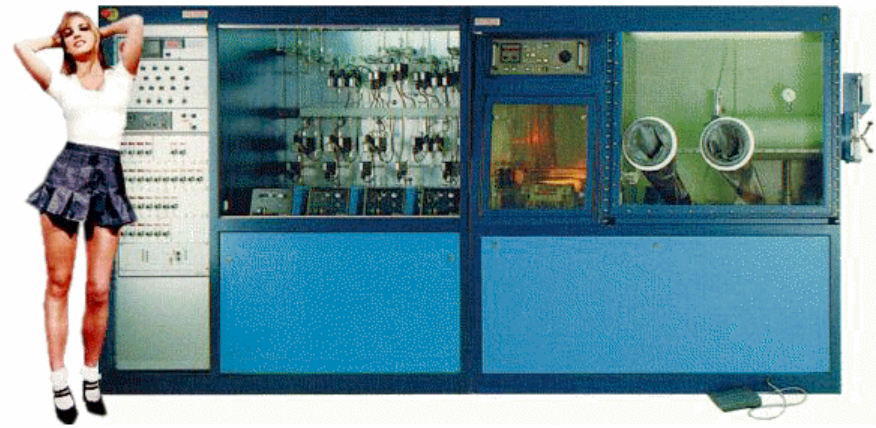
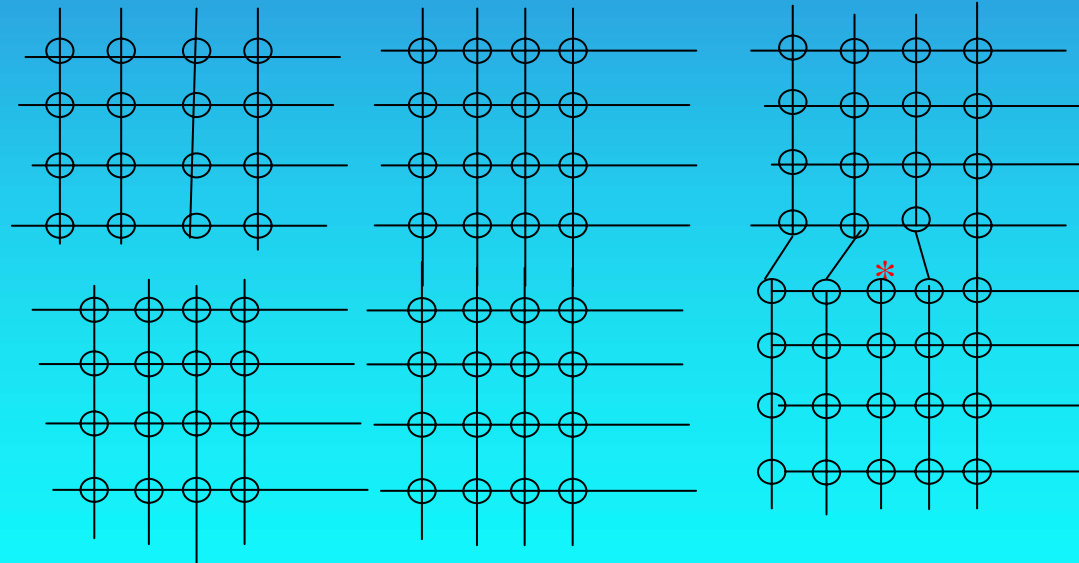


Figure 4. Schematic diagram of the MOCVD process



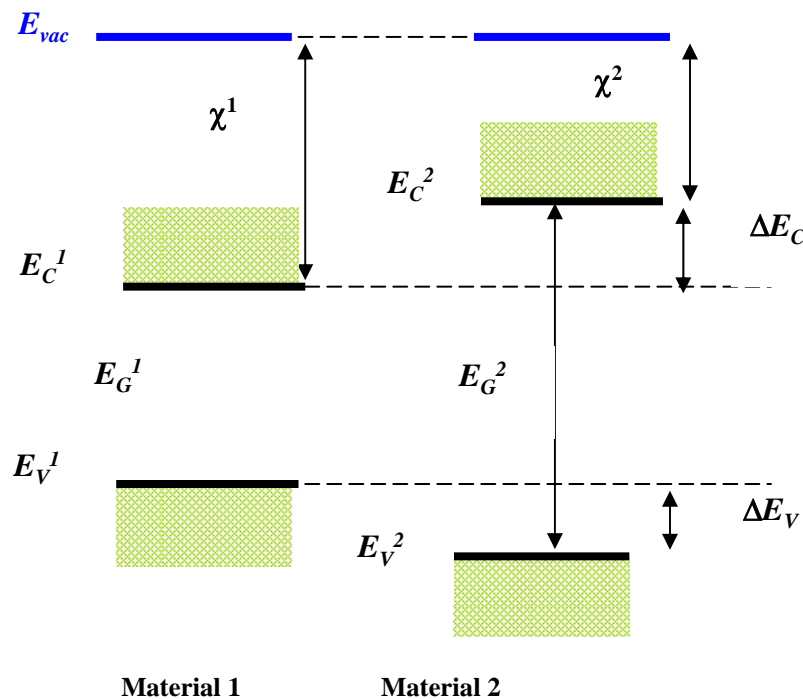
strain due to lattice mismatch

InGaAs



GaAs

Energy band offsets

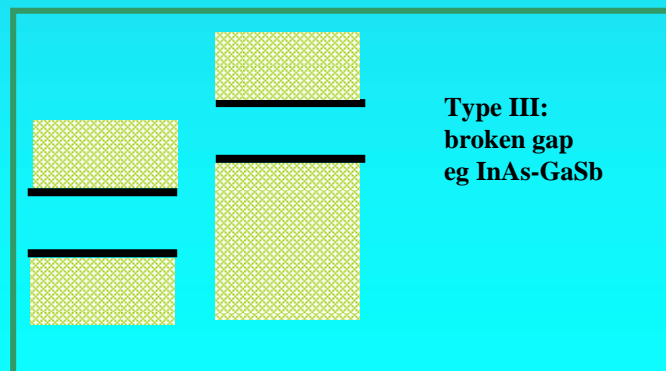
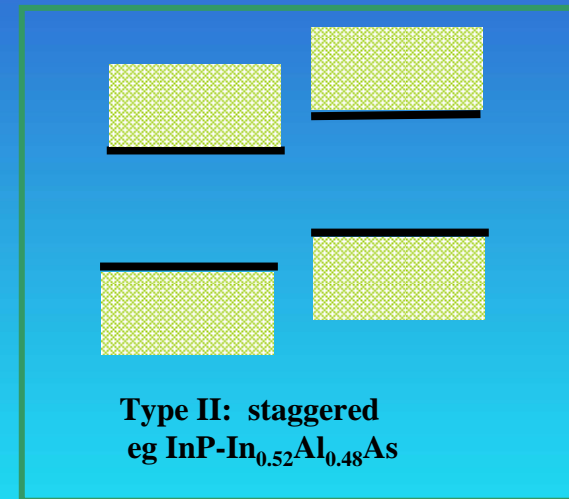
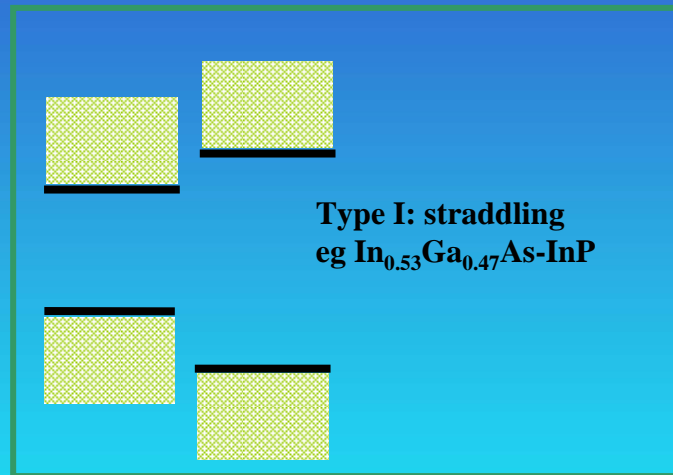


Electron affinity χ :
Energy required to remove an electron from the conduction band and take it to the vacuum.

$$\Delta E_C = \chi^1 - \chi^2$$

$$\Delta E_V = E_G^1 - E_G^2 - \Delta E_C$$

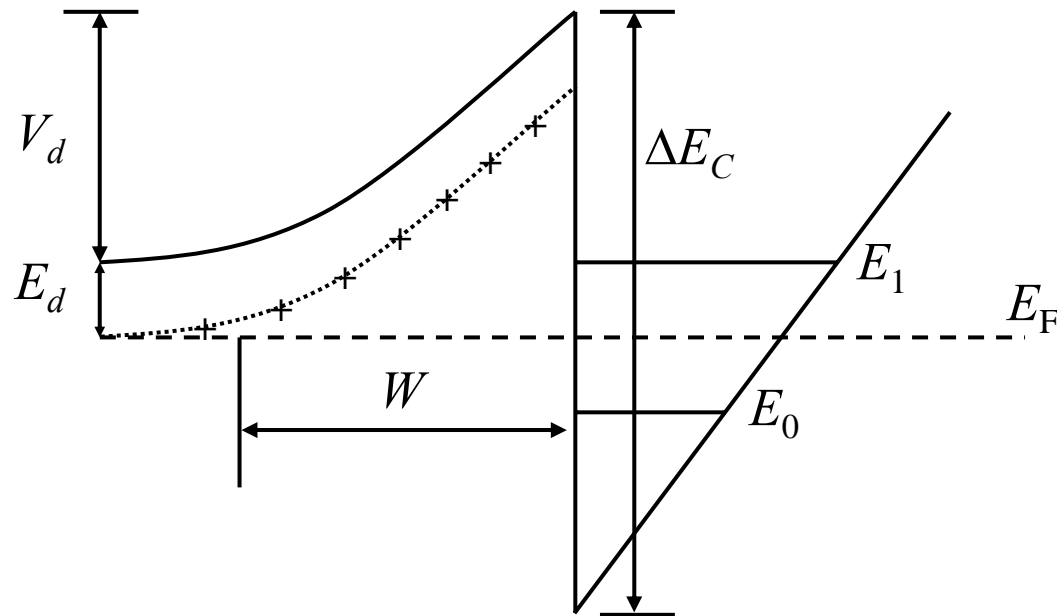
Heterostructure band alignment



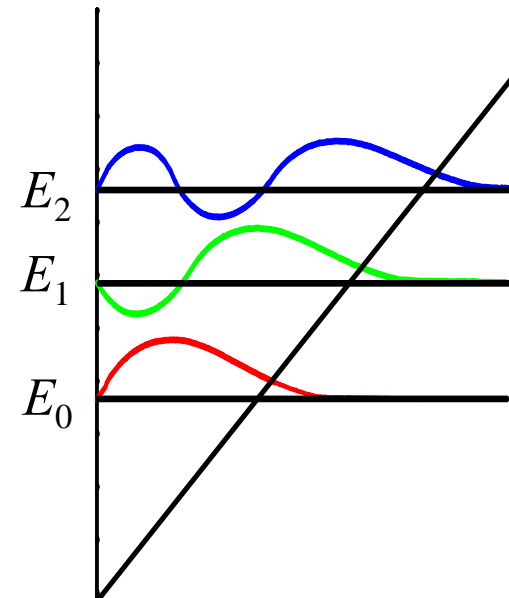
These examples of band alignment show how the potential barrier across a *pn* junction may be increased (Type I), electronic states can be made "spatially indirect" (Type II), or semi-metallic behaviour can be produced due to overlapping conduction and valence bands (Type III).

A single heterojunction

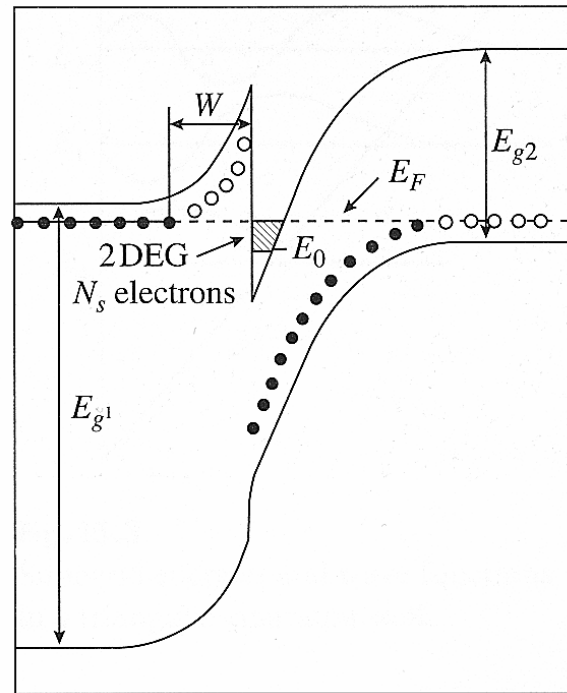
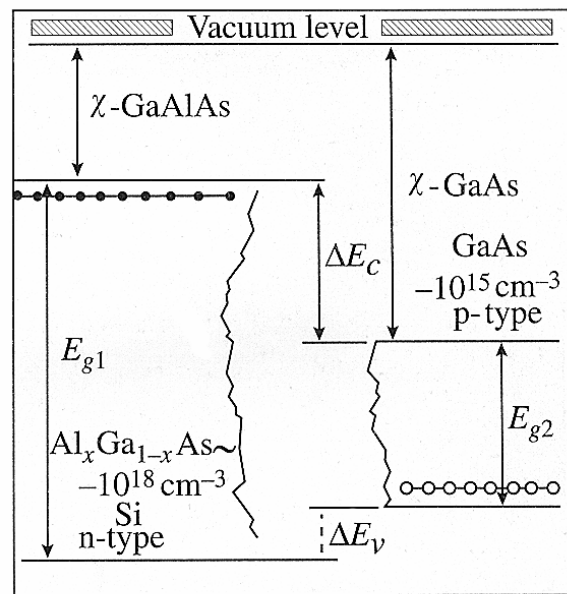
energy bands



wavefunctions



A single heterojunction



$$\mathfrak{T} = \frac{N_s e}{\epsilon_0 \epsilon_r} \quad \text{and for } z > 0 \text{ for a triangular well:}$$

$$\varphi(z) = -\mathfrak{T}z \quad \text{so solving Schrodinger's equation gives:}$$

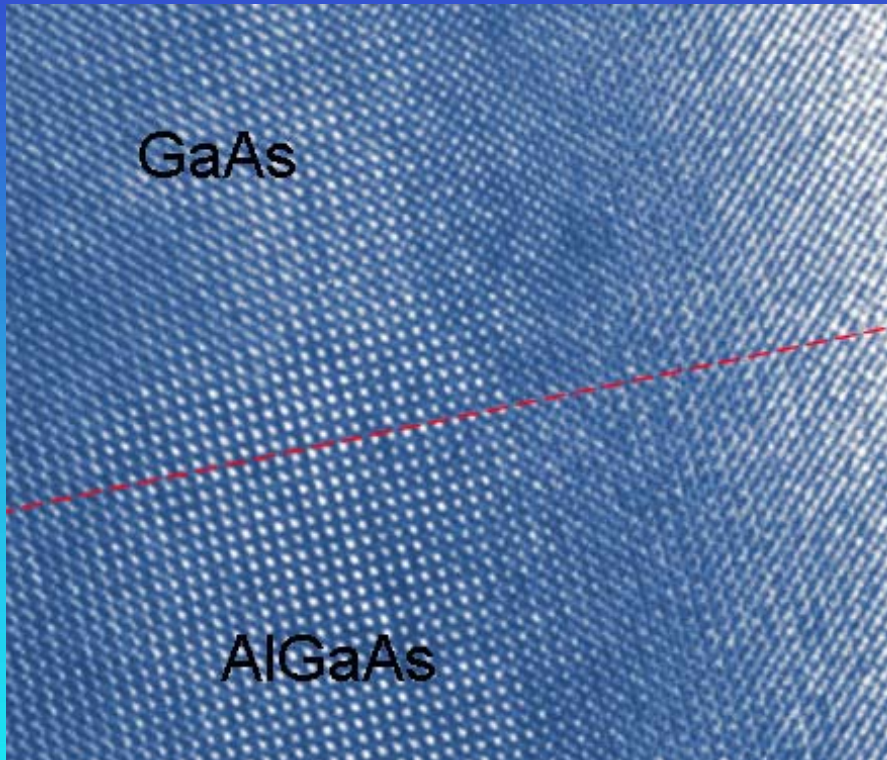
$$E_n = -\left(\frac{e^2 \mathfrak{T}^2 \hbar^2}{2m^*}\right)^{1/3} a_n$$

$$a_n \cong -\left[\frac{3\pi}{2}(n + 3/4)\right]^{2/3}, \quad n = 0, 1, \dots$$

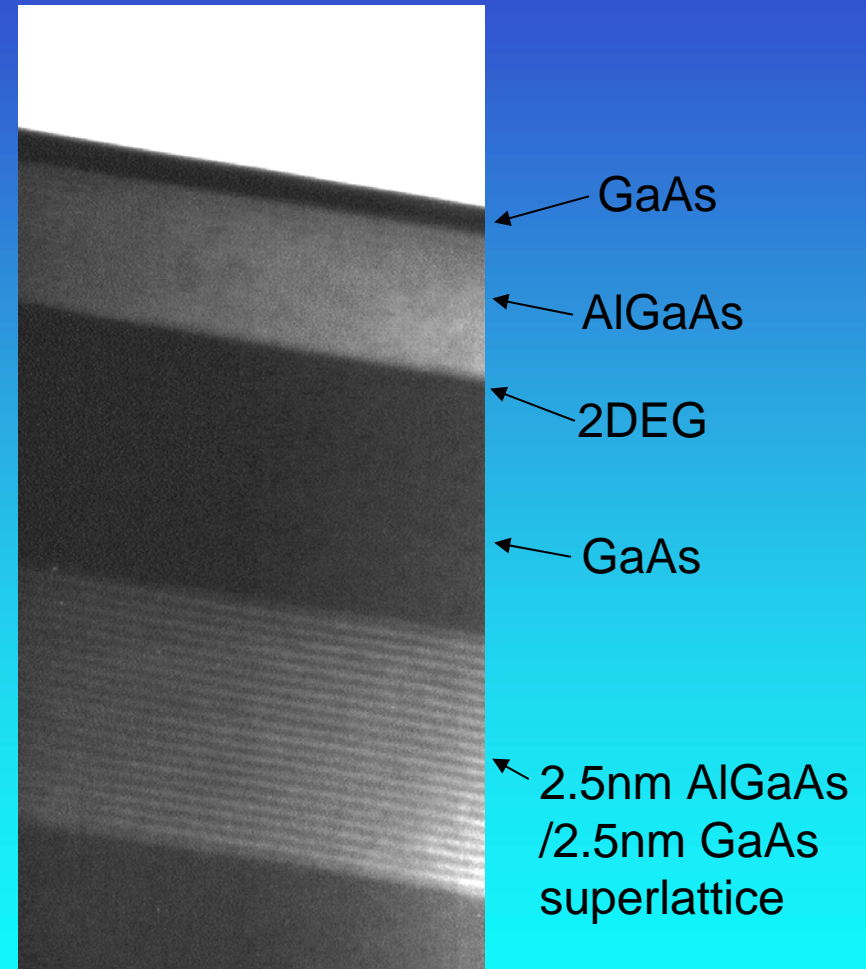
$$E_n \cong \left(\frac{\hbar^2}{2m^*}\right)^{1/3} \left[\frac{3\pi e \mathfrak{T}}{2}(n + 3/4)\right]^{2/3} \quad \text{and eliminating } \mathfrak{T}$$

$$E_0 \cong \left(\frac{\hbar^2}{2m^*}\right)^{1/3} \left(\frac{9\pi e^2 N_s}{8\epsilon_0 \epsilon_r}\right)^{2/3}$$

A perfect junction?



High Resolution TEM GaAs/AlGaAs interface (T Walther, Materials)



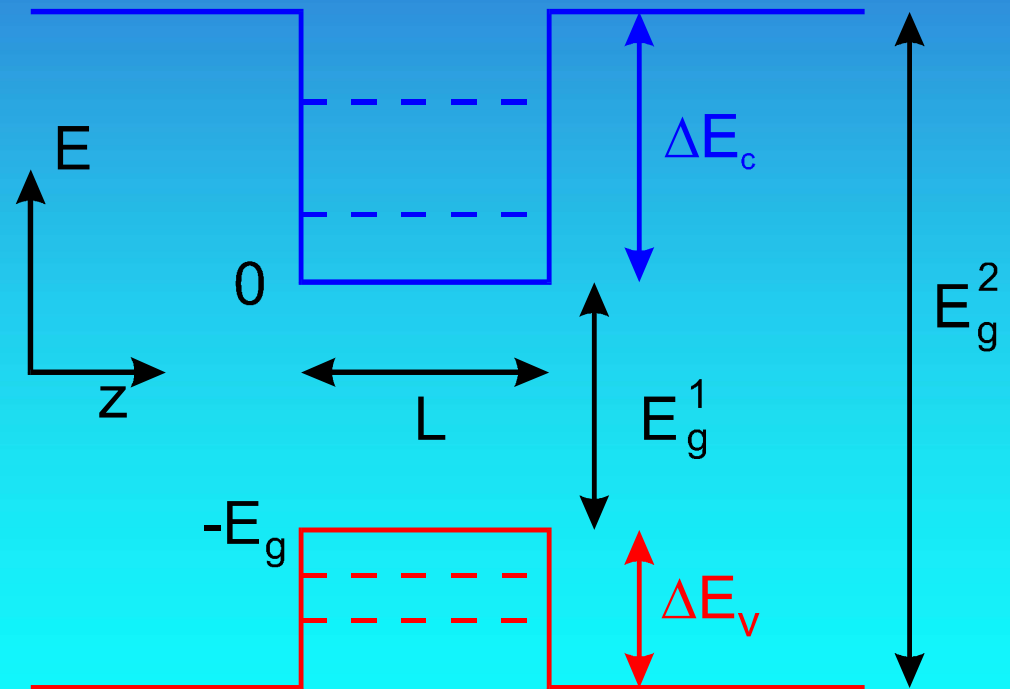
TEM of GaAs/AlGaAs 2DEG structure with superlattice buffer (W M Stobbs, Materials)

Quantum Well - Type I

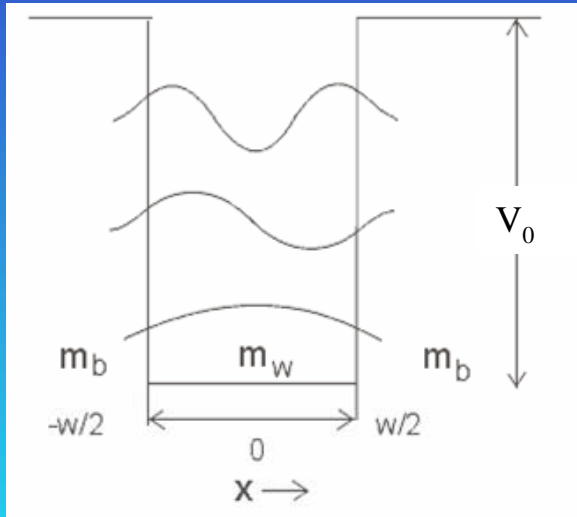
Typical Materials: 1: GaAs ($E_g = 1.5 \text{ eV}$) 2: $(\text{Al}_{0.35}\text{Ga}_{0.65})\text{As}$ ($E_g = 2.0 \text{ eV}$)

Energy levels are quantized in z-direction with values E_n for both electrons and holes \therefore

$$E = \underset{\substack{\uparrow \\ \text{1-D}}}{E_n} + \underset{\substack{\uparrow \\ \text{2-D}}}{\hbar^2 k_{\perp}^2 / 2m^*}$$



particle in a finite potential well



The continuity conditions at the interfaces are that ψ and $\frac{1}{m} \frac{\partial \psi}{\partial x}$ should be continuous.

$$\psi_n(x) = A \cos kx \quad \text{for } |x| < w/2$$

$$= B \exp \left[-K \left(x - \frac{w}{2} \right) \right] \quad \text{for } x > w/2$$

$$= B \exp \left[+K \left(x + \frac{w}{2} \right) \right] \quad \text{for } x < -w/2$$

$$\left(-\frac{\hbar^2}{2m_w} \frac{\partial^2}{\partial^2 x} - V_0 \right) \psi_n(x) = \varepsilon_n \psi_n(x)$$

$$\psi_n(x) = A \sin kx \quad \text{for } |x| < w/2$$

$$= B \exp \left[-K \left(x - \frac{w}{2} \right) \right] \quad \text{for } x > w/2$$

$$\left(-\frac{\hbar^2}{2m_b} \frac{\partial^2}{\partial^2 x} \right) \psi_n(x) = \varepsilon_n \psi_n(x)$$

$$= B \exp \left[+K \left(x + \frac{w}{2} \right) \right] \quad \text{for } x < -w/2$$

Eigenvalues for finite potential well

$$A \cos\left(\frac{kw}{2}\right) = B$$

$$\frac{k}{m_w} A \sin\left(\frac{kw}{2}\right) = \frac{KB}{m_b}$$

$$\therefore \frac{k}{m_w} \tan\left(\frac{kw}{2}\right) = \frac{K}{m_b}$$

$$A \sin\left(\frac{kw}{2}\right) = B$$

$$\frac{k}{m_w} A \cos\left(\frac{kw}{2}\right) = -\frac{KB}{m_b}$$

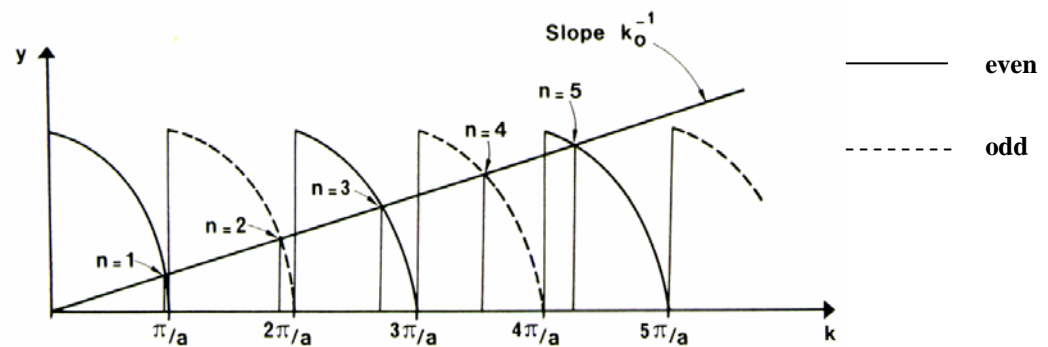
$$\therefore \frac{k}{m_w} \cot\left(\frac{kw}{2}\right) = -\frac{K}{m_b}$$

$$m_w \neq m_b$$

$$\cos\frac{kw}{2} = \frac{k}{k_0} \quad \text{for} \quad \tan\left(\frac{kw}{2}\right) > 0$$

$$\sin\frac{kw}{2} = \frac{k}{k_0} \quad \text{for} \quad \tan\left(\frac{kw}{2}\right) < 0$$

$$k_0^2 = \frac{2mV_0}{\hbar^2}$$



$$m_w = m_b$$

Density of States

Travelling waves

$$e^{ikx} \quad (e^{i\mathbf{k}\cdot\mathbf{r}})$$

Periodic boundary conditions

$$\psi(x) = \psi(x + L)$$

$$\therefore e^{ikL} = 1 \rightarrow k = \pm 2n\pi/L$$

$$\rightarrow \delta k = 2\pi/L$$

$$\varepsilon = \hbar^2 k^2 / 2m^*,$$

$$d\varepsilon = (\hbar^2 / 2m^*) 2k dk$$

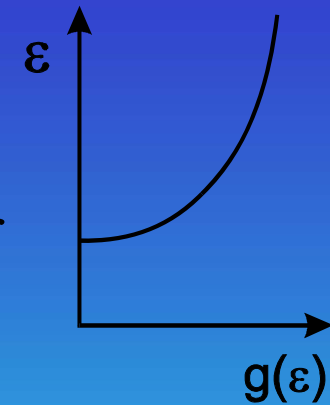
$$g(k)dk$$

3-D

$$\frac{4\pi k^2 dk}{(2\pi / L)^3}$$

$$g(\varepsilon)d\varepsilon$$

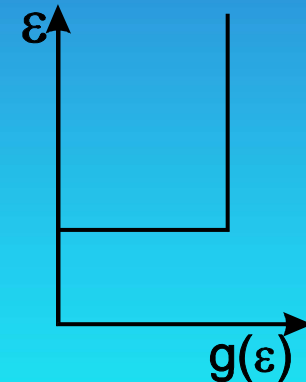
$$\frac{V}{(2\pi)^2} \left(\frac{2m^*}{\hbar^2} \right)^{3/2} \varepsilon^{1/2} d\varepsilon$$



2-D

$$\frac{2\pi k dk}{(2\pi / L)^2}$$

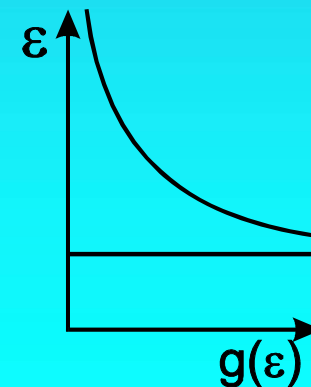
$$\frac{A}{4\pi} \left(\frac{2m^*}{\hbar^2} \right) d\varepsilon$$



1-D

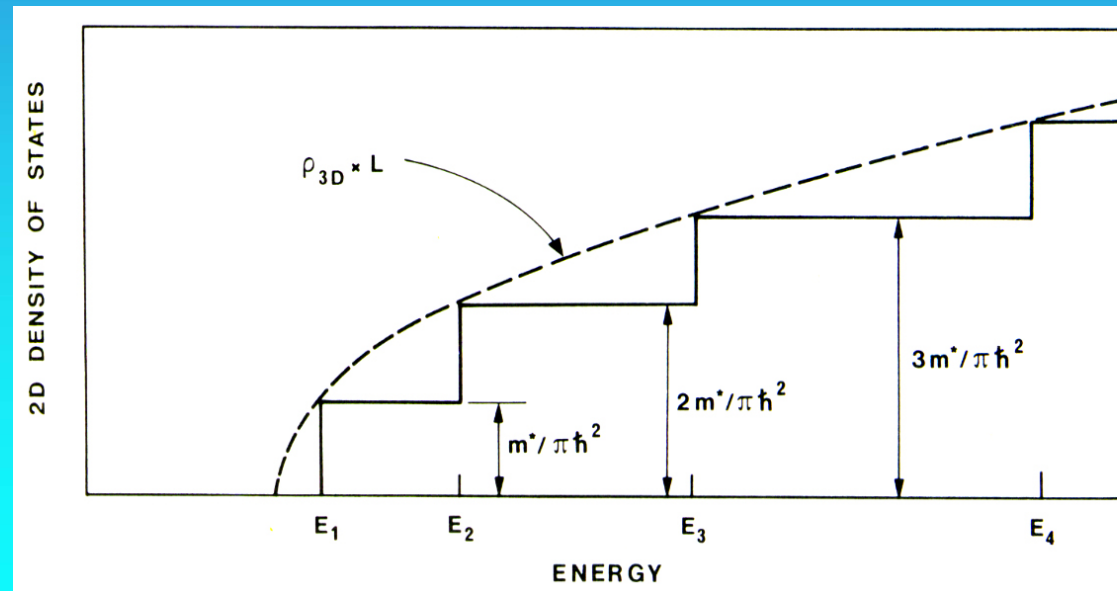
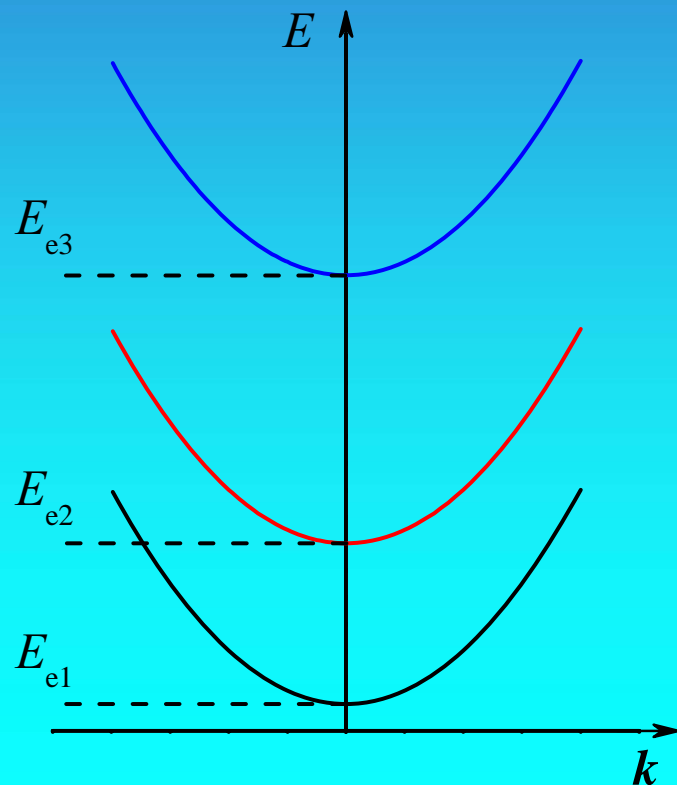
$$\frac{2dk}{2\pi / L}$$

$$\frac{L}{2\pi} \left(\frac{2m^*}{\hbar^2} \right)^{1/2} \varepsilon^{-1/2} d\varepsilon$$

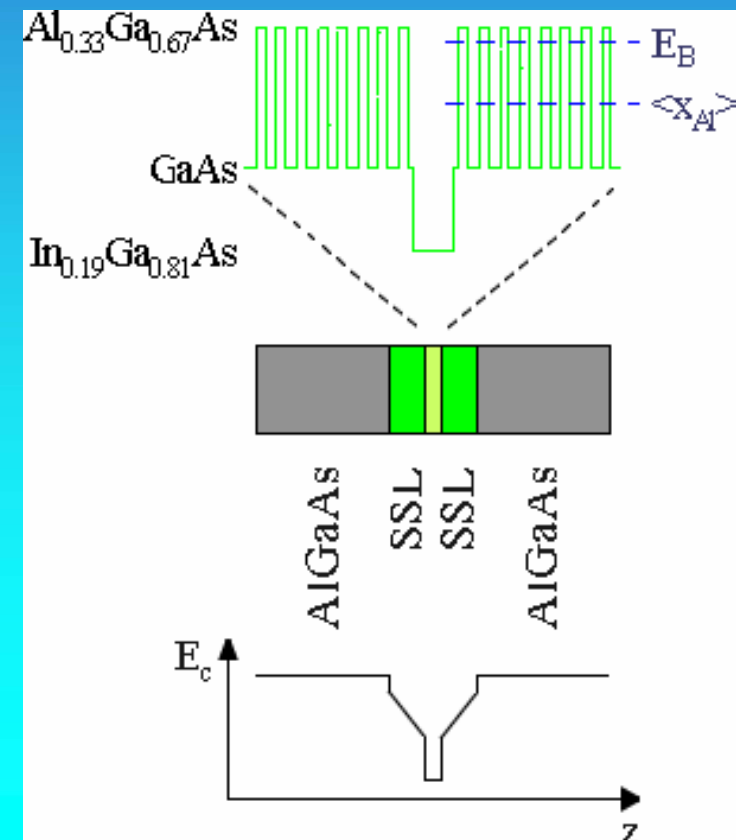
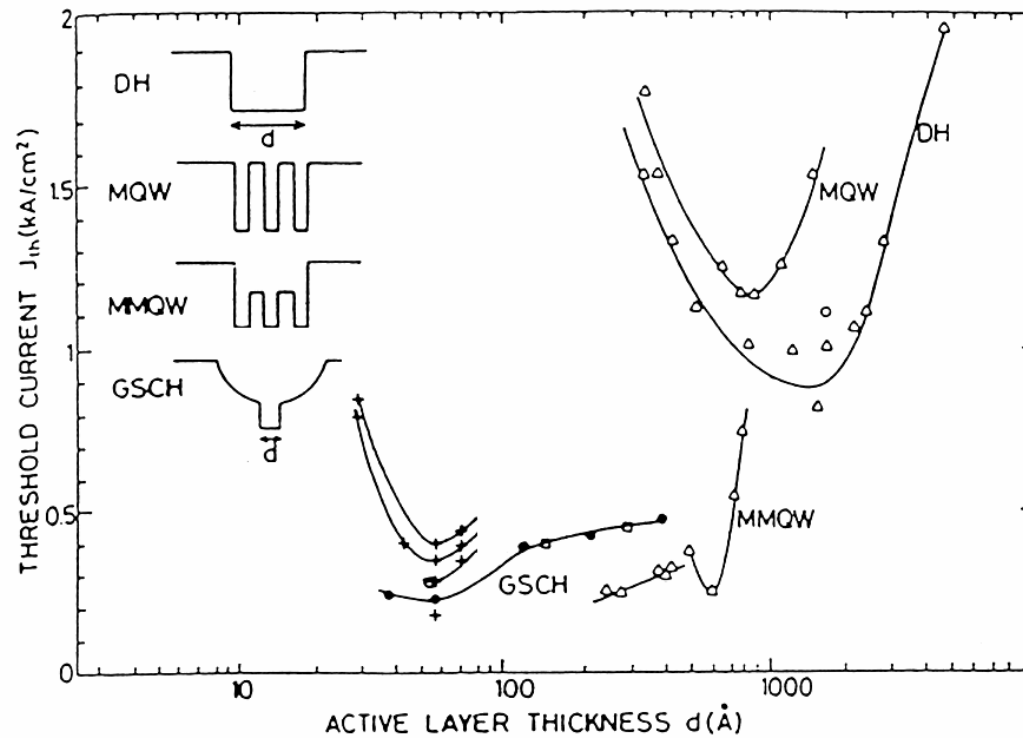


Two-dimensional density of states

$$E_n = \frac{\pi^2 \hbar^2 n^2}{2m^* w^2} + \frac{\hbar^2 k_x^2}{2m^*} + \frac{\hbar^2 k_y^2}{2m^*}$$



Quantum well lasers



Band structure engineering of a quantum well laser

